L Number	Hits	Search Text	DB	Time stamp
69	1154	(("257/620") or ("438/906") or ("437/83") or ("437/84") or ("117/19") or ("117/84")).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:08
70	1	((("257/620") or ("438/906") or ("437/83") or ("437/84") or ("117/19") or ("117/84")).CCLS.) and (hydrogen with dop$3 with silicon with wafer) same concentration	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:09
71	90	((("257/620") or ("438/906") or ("437/83") or ("437/84") or ("117/19") or ("117/84")).CCLS.) and czochralski	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:10
72	18	((("257/620") or ("438/906") or ("437/83") or ("437/84") or ("117/19") or ("117/84")).CCLS.) and heat adj shield	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:11
73	37	((("257/620") or ("438/906") or ("437/83") or ("437/84") or ("117/19") or ("117/84")).CCLS.) and nitrogen with dop$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:11
74	43	((("257/620") or ("438/906") or ("437/83") or ("437/84") or ("117/19") or ("117/84")).CCLS.) and (argon with hydrogen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:12
75	201	((("257/620") or ("438/906") or ("437/83") or ("437/84") or ("117/19") or ("117/84")).CCLS.) and oxidation	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:12
76	1	single adj silicon adj crystal.ti,ab. and czochralski.ti,ab. and nitrogen.ti,ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:14
77	54	silicon adj single adj crystal.ti,ab. and czochralski.ti,ab. and nitrogen.ti,ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:14
78	805	("117/13").CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:17
79	0	(("117/13").CCLS.) and heat adj sjield.ti,ab. and czochralski	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:17
80	5	(("117/13").CCLS.) and heat adj shield.ti,ab. and czochralski	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/01/05 19:17